

Porous Material Air Bearing Platen for Chemical Mechanical Planarization

ABSTRACT OF THE DISCLOSURE

A platen for use in chemical mechanical planarization (CMP) systems includes a platen plate that has at least one recess defined therein. The at least one recess has an input port formed therein. A porous material is disposed in the at least one recess. The porous material has a porosity sufficient to restrict air flow therethrough so as to reduce an amount of air required for a CMP operation.

Patent # 7,546,001